

ETCHING OF CHROMIUM FILM

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Abstract

PROBLEM TO BE SOLVED: To provide a method for etching a chromium film by which the shape of the etching taper of a chromium-film circuit is stabilized.

SOLUTION: An etching photoresist is formed on a chromium film by photolithography (S1 to S3), the etching photoresist is dipped in hot water at 50-100 deg.C (S4), and then the chromium film not covered with the photoresist is etched by an aq. soln. contg. 10-20 wt.% ammonium ceric nitrate and 5-10 wt.% nitric acid (S5).

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